

ABSTRACT

To provide a photocurable composition from which a cured product excellent in mold release characteristics and mechanical strength can be obtained, and a method for
5 producing a molded product excellent in durability, with a fine pattern having a reverse pattern of a mold precisely transferred on its surface.

A photocurable composition 20 comprising from 15 to 60 mass% of a compound (A) which is an aromatic compound
10 having at least two rings or an alicyclic compound having at least two rings and which has two (meth)acryloyloxy groups, from 5 to 40 mass% of a compound (B) having a fluorine atom and having at least one carbon-carbon unsaturated double bond (excluding the compound (A)),
15 from 10 to 55 mass% of a compound (C) having one (meth)acryloyloxy group (excluding the compound (B)) and from 1 to 12 mass% of a photopolymerization initiator (D) (provided that $(A)+(B)+(C)+(D)=100$ mass%) is used.